SM-150 Laboratory Spin Coater

English selection sheet | Prepared from public manufacturer specifications



A Swiss manual spin coater for thin photoresist films on flat or low-topography substrates in laboratory and process-development work.

Portable bench-top and bench-mounted versions are available. Select a chuck for the actual sample dimensions, thickness, shape and backside contact area.

Model and configuration

Wafer / square substrate	Up to 150 mm (6 inches) / 127 x 127 mm
Rotation speed	0-10,000 rpm; nominal accuracy +/-1 rpm
Recipe control	Up to 50 programs, with 24 segments each
Loading and fixation	Manual loading/unloading; vacuum fixation and guard
Optional dispensing	50 ml glass cartridge, manual arm and suck-back
Installation	Portable bench-top or bench-mounted configuration

Maximum wafer size does not define a minimum fragment size. Confirm small-piece fixation and film performance with the actual samples and resist. A separate HP-150 or the two-station Duo adds baking; this is not heating inside the spin chamber.

Specifications and independent equipment record

Manufacturer: SM-150 specifications →

EPFL CMI: SM-150 for small pieces and 150 mm wafers →

China website: English SM-150 configuration page →

Prepared by the China team; this is not a manufacturer-issued technical datasheet. Institutional listings identify equipment and use, rather than endorsements or standard options for every order. Final scope follows the confirmed configuration.

Shenzhen Ruixun Semiconductor Systems Co., Ltd.
16D, Building 1, Qiaochengfang, 4080 Qiaoxiang Road, Nanshan, Shenzhen, China
+86 755 8695 0873 | nova@sawatec.com.cn | sawatec.com.cn